	Hits	Search Text	DBs
40	114	(((stor$4 near9 device) or container or holder or bath) same (liquid or solvent or solution or ether or (TPM near6 ether) or ($4propylene near8 glycol near12 ether)) same ((remov$4 or dissolv$4 or strip$4 or eliminat$4) near16 (wafer or substrate) near16 (resin$4 or photoresist or resist) near29 (submers$4 or immers$4)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
41	153	(((stor$4 near9 device) or container or holder or bath) same (liquid or solvent or solution or ether or (TPM near6 ether) or ($4propylene near8 glycol near12 ether)) same (remov$4 or dissolv$4 or strip$4 or eliminat$4) same ((wafer or substrate) near16 (resin$4 or photoresist or resist) near29 (submers$4 or immers$4) near19 (bath or container or holder or storage)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	107	(((stor$4 near9 device) or container or holder or bath) same (liquid or solvent or solution or ether or (TPM near6 ether) or ($4propylene near8 glycol near12 ether)) same (remov$4 or dissolv$4 or strip$4 or eliminat$4) same ((wafer or substrate) near16 (resin$4 or photoresist or resist) near29 (submers$4 or immers$4) near19 (bath or container or holder or storage) near29 (solvent or solution or ether or liquid)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
43	64	(((stor$4 near9 device) or container or holder or bath) same (liquid or solvent or solution or ether or (TPM near6 ether) or ($4propylene near8 glycol near12 ether)) same (remov$4 or dissolv$4 or strip$4 or eliminat$4) same ((wafer or substrate) near16 (resin$4 or photoresist or resist) near29 (submers$4 or immers$4) near19 (bath or container or holder or storage) near29 (solvent or solution or ether or liquid))) and ((resin or photoresist or resist) near16 (substrate or wafer) near20 (expos$4 or illuminat$4 or irradiat$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB